Errata

G. W. LEWIS, J. S. COLLIGON and M. J. NOBES, *J. Mater. Sci.* **15** (1980) 681.

p. 682 The captions to Figures 1 and 2 should be interchanged

p. 683 Figure 3 was printed in an incomplete form. The corrected figure is given below.

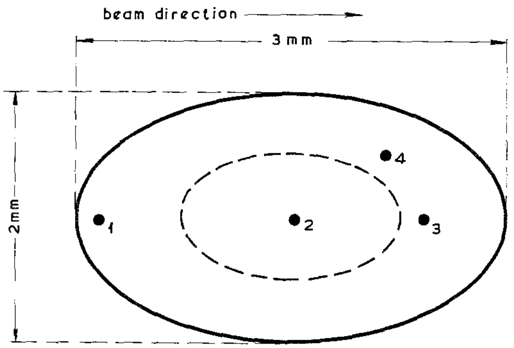

Figure 3 Static experiment for Ar^+ on silicon. Micrographs refer to surface structure appropriate to the areas indicated. Total dose at the centre (2), neglecting secondary electron and neutral atom contributions, is 7.4×10^{19} ions cm^{-2}. In all micrographs the ion beam projected direction is towards the lower right-hand corner. Micrographs 1 to 4 are to the scale indicated in 1.